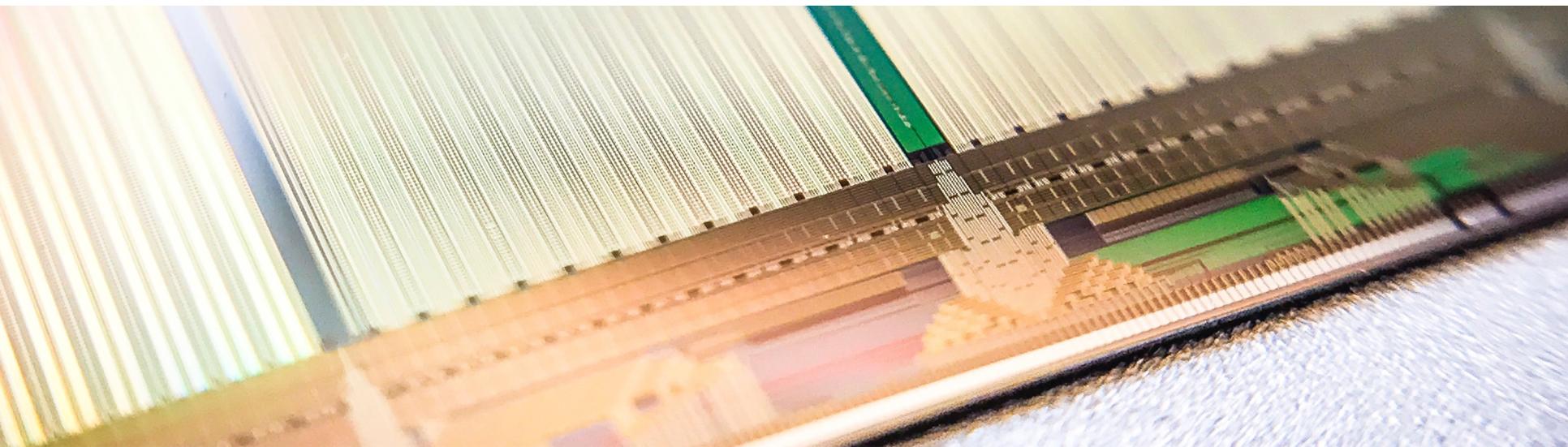




HV-CMOS Active Pixel Sensors

CCPDs: From design simulations to testbeam

R&D for the ITk ATLAS HL-LHC Upgrade



H35DEMO 100 μm thick

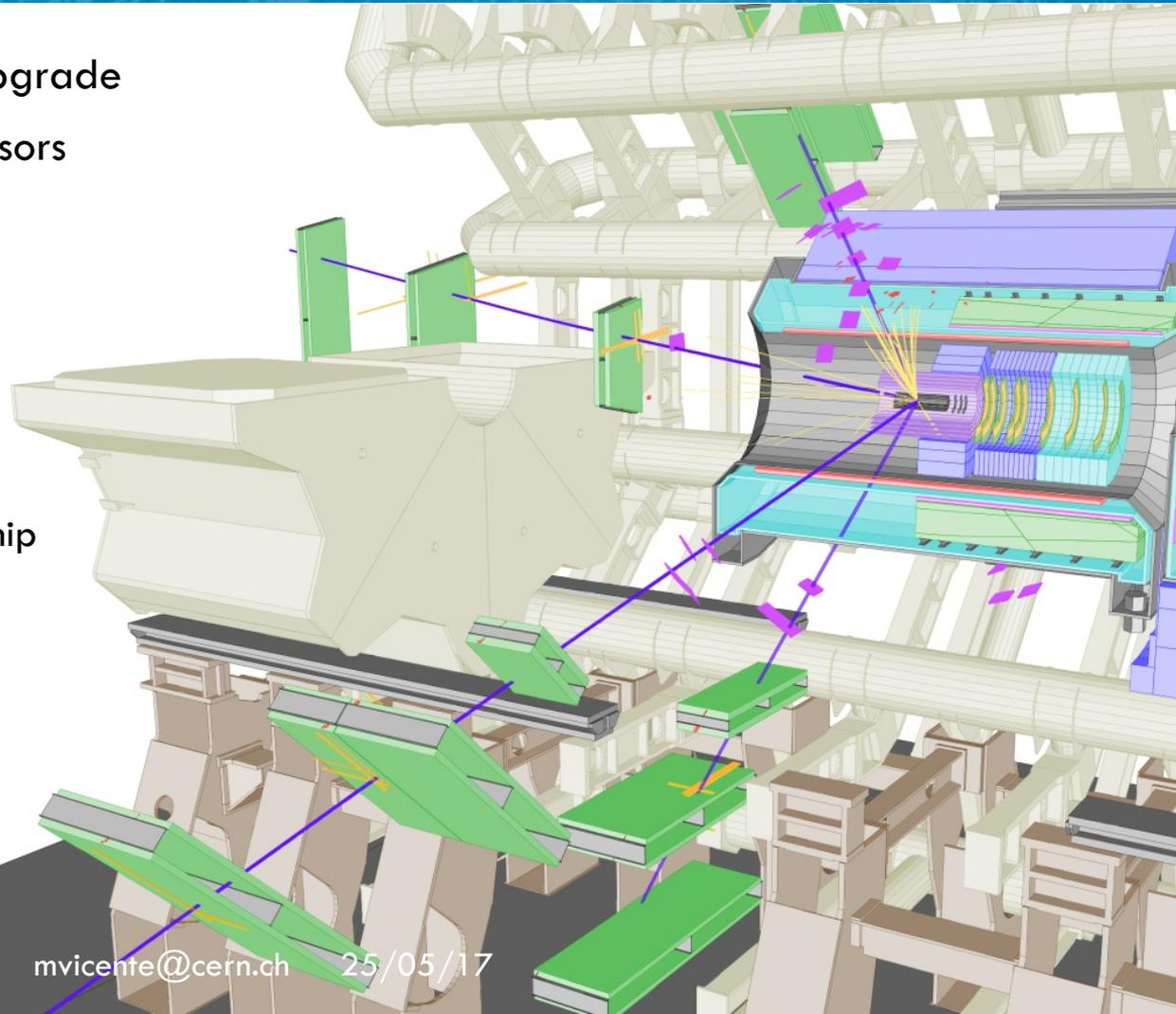
TIPP2017 – R4(5)
25/05/2017

Mateus Vicente (UniGE/CERN)
on behalf of the ATLAS HV-CMOS UniGE collaboration

Talk outline

2

- The ATLAS Inner Tracker Upgrade
 - HV-CMOS Active Pixel Sensors
 - ▣ HV-CMOS sensor concept
 - H35DEMO CCPD
 - ▣ TCAD simulations
 - ▣ TCT measurements
- Assembling
 - ▣ Wafer probing and flip-chip
- Caribou DAQ system
- Characterization
 - ▣ Testbeam measurements
- Summary and Conclusions

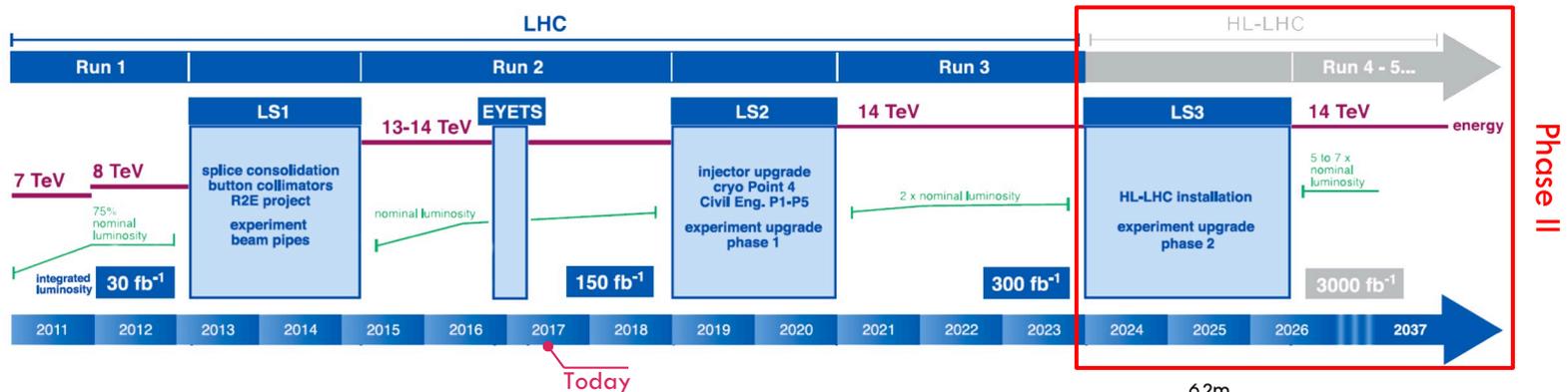


ATLAS Inner Tracker

All-silicon tracker upgrade

3

- Luminosity upgrade on LHC to improve measurements and searches

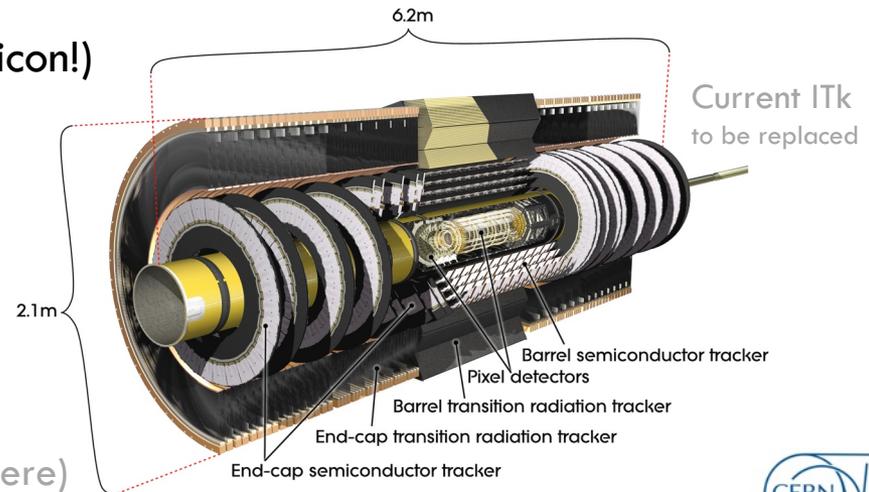


- New all-silicon inner tracking ($\sim 200\text{m}^2$ of silicon!)

- Candidate for some detector layers:

New **HV-CMOS** Active Pixel Sensors

- Commercial process \rightarrow **Low cost**
- Capacitively Coupled Pixel Detector (**CCPD**)
 - Bump-bonds are changed by glue
- HV-CMOS Monolithic Detectors (not covered here)

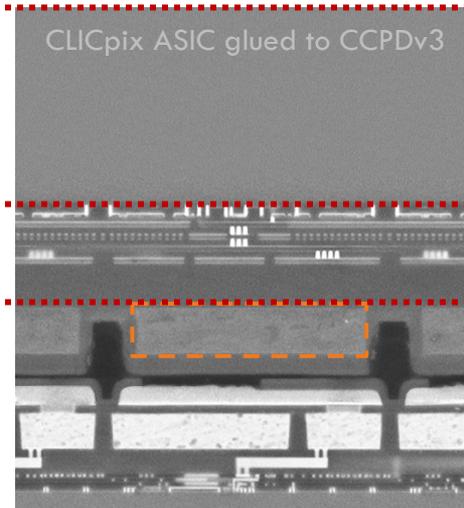
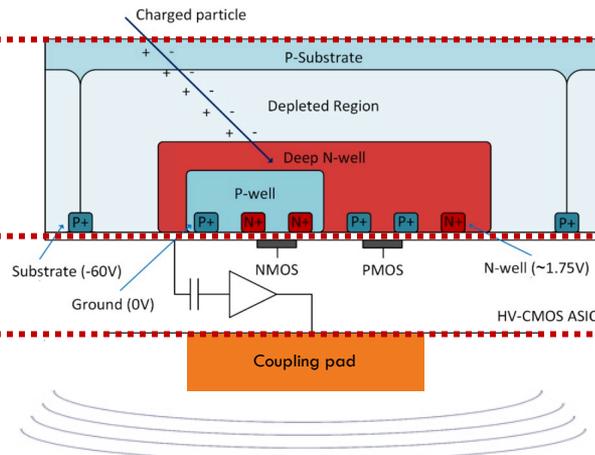


ATLAS Inner Tracker

HV-CMOS CCPDs

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- New **HV-CMOS** technology being investigated
 - ▣ High Voltage can be applied on silicon sensor **bulk** (for **fast charge collection** like on planar sensors) where the the transistors of a readout **CMOS circuitry** is also implanted
 - **CMOS** transistors **shielded from bulk HV** by **Deep N-well implant** (sensor **collecting diode**)
 - The **signal** generated by a particle in the sensor bulk is already **processed in the sensor**
 - **Amplification** of the signal to cope with a **capacitive coupling** between sensor and readout chip



Substrate bulk +
CMOS transistors

HV-CMOS circuitry

HV-CMOS pixel
coupling pad

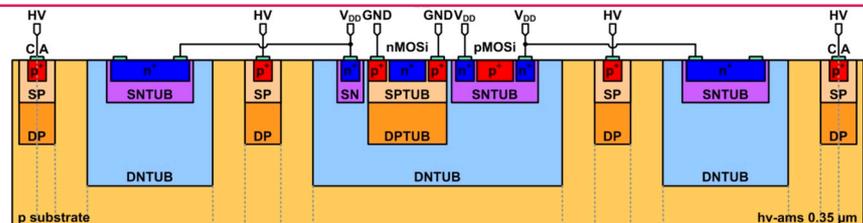
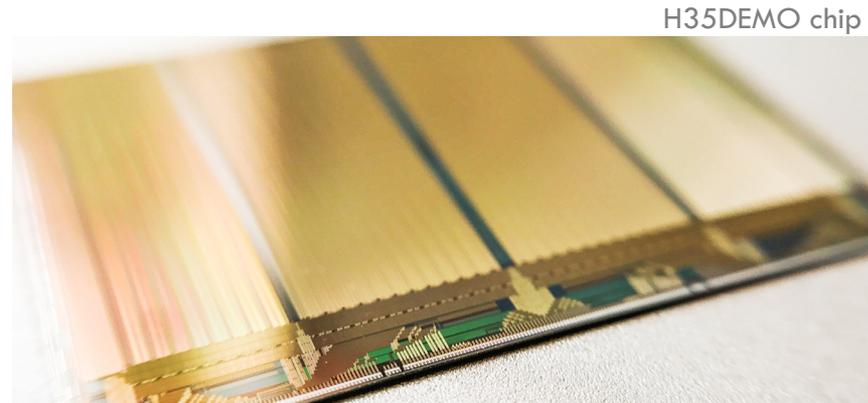
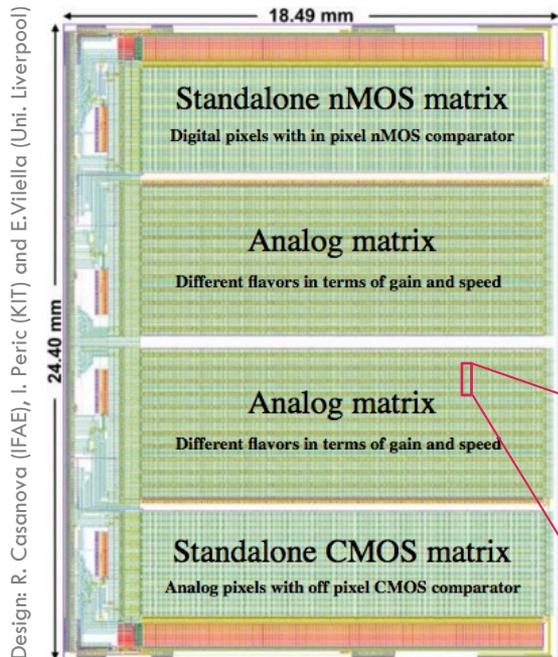
Readout ASIC

HV-CMOS H35DEMO Pixel Sensor

General description

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- Demonstrator Pixel Sensor chip implemented in a **350 nm HV-CMOS** process
 - ▣ Pixel pitch of **50x250 μm** (matching FE-I4 readout chip foot print)
 - ▣ **Different pixels and readout types** with differences in the **electronic circuits**
 - All pixels flavors has the **same implants structure**

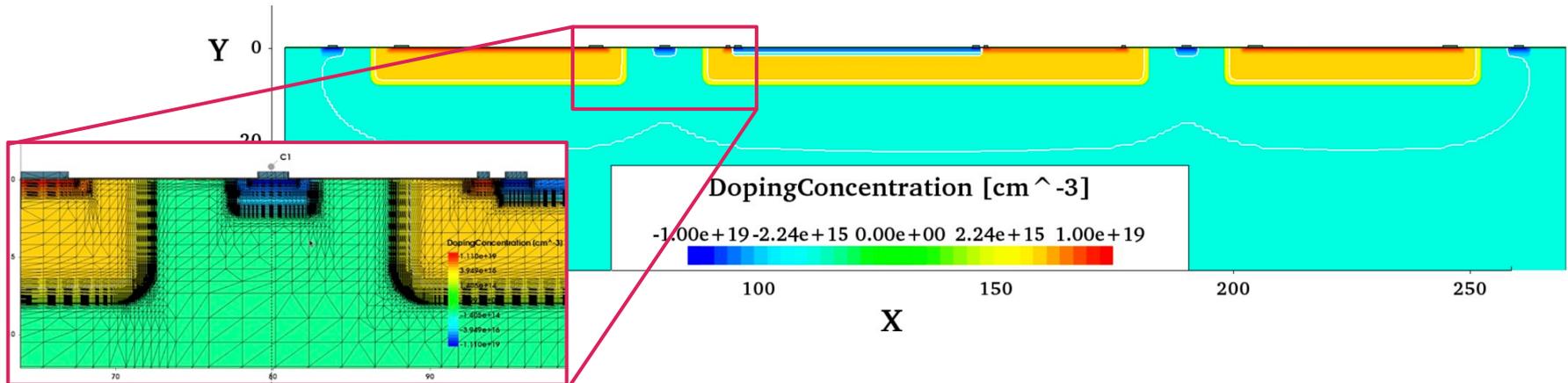


HV-CMOS H35DEMO Pixel Sensor

TCAD simulations

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- **TCAD simulations** to analyse design of the pixel implants and circuit transistors
 - Different **wafer resistivities** available from the foundry
 - **20, 80, 200** and **1000** Ohm*cm
 - Difference between devices **biased** from the **top** and from the **back**
 - Study of sensor **general features and behavior**
 - Leakage current; charge collection (from drift and/or diffusion); signal evolution; etc...

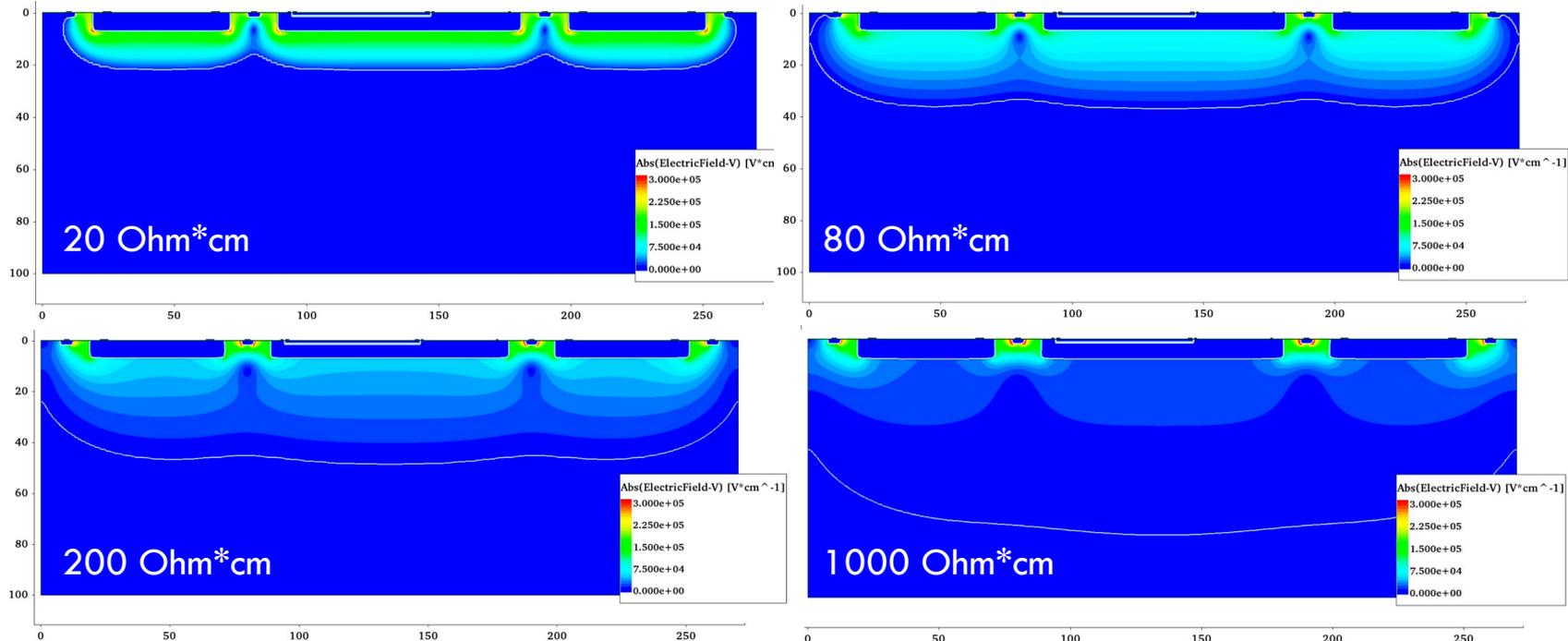


HV-CMOS H35DEMO Pixel Sensor

TCAD simulations – Different resistivities

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- Comparison of the electric field between 20, 80, 200 and 1000 Ohm*cm



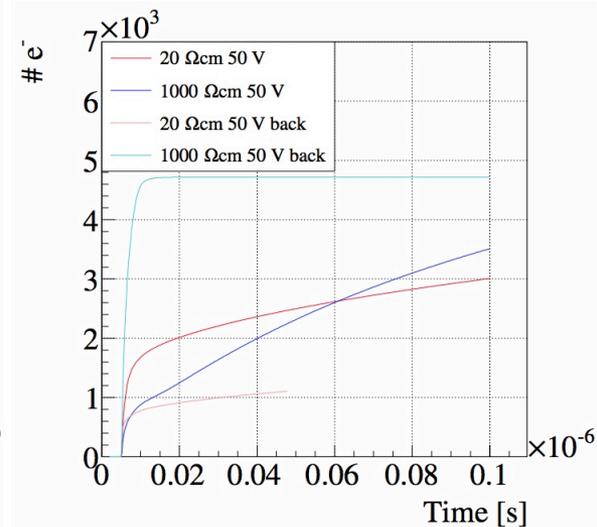
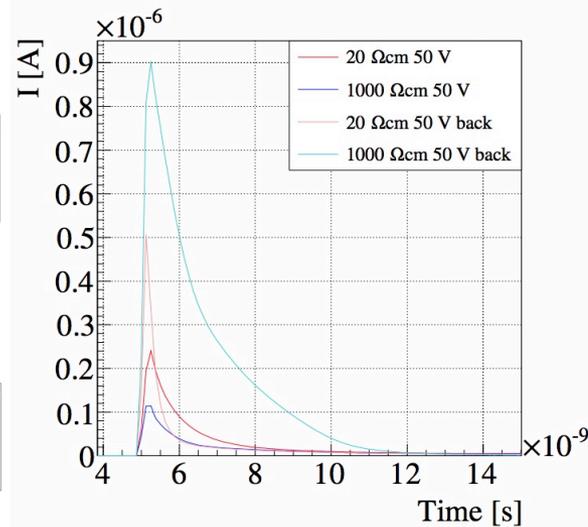
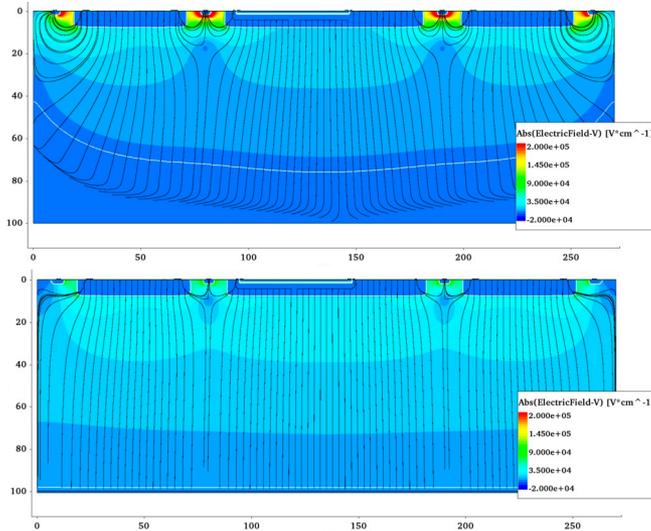
- While lower resistivities has higher electric field close to the collection diode, higher resistivities leads to larger depletion zone

HV-CMOS H35DEMO Pixel Sensor

TCAD simulations – Different biasing

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- Possibility to process the devices back side, allowing to bias the sensor from the back plane (opposite to the collection diode)
 - ▣ Visible effect on electric field intensity and charge collection efficiency
 - **Larger depletion zone** for the same bias voltage
 - Combined with higher substrate resistivity can lead to **faster and higher charge collection**

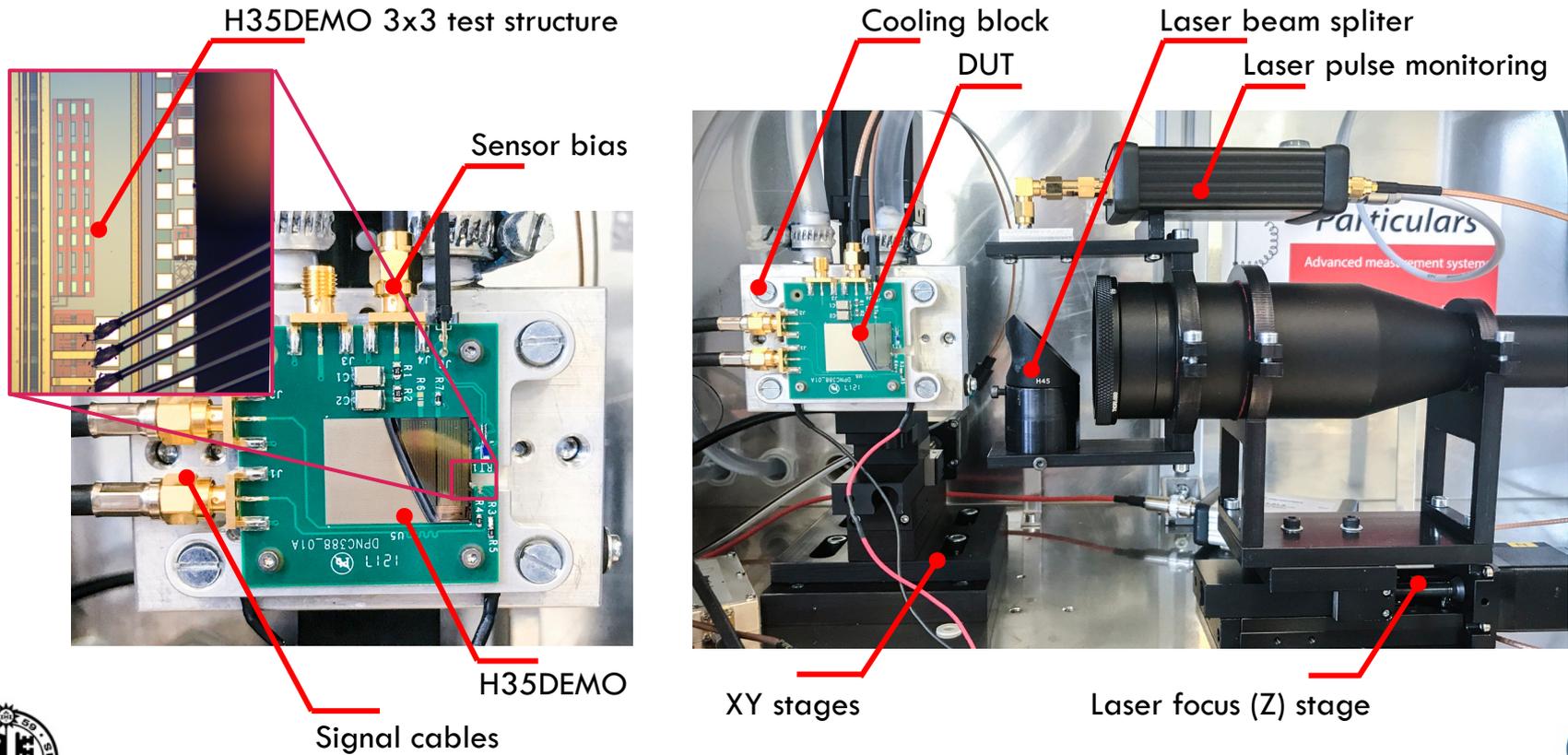


HV-CMOS H35DEMO Pixel Sensor

TCT measurements – Setup

9

- Red (660 nm) and infrared (1060 nm) laser for **top** and **edge** TCT measurements



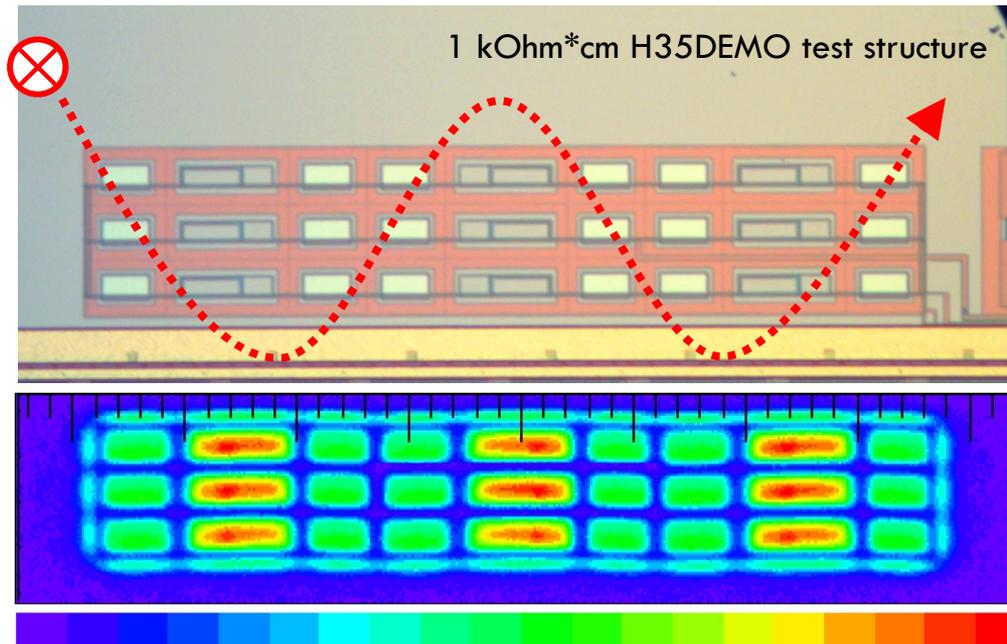
HV-CMOS H35DEMO Pixel Sensor

TCT measurements – Top surface scan

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- Scan over the surface with a 1064 nm laser
 - ▣ Record of **each current pulse** generated by the laser hit on each position
 - ▣ Penetration depth of **~1 mm**
 - ▣ Clear visibility of pixel collection diodes

1064 nm laser

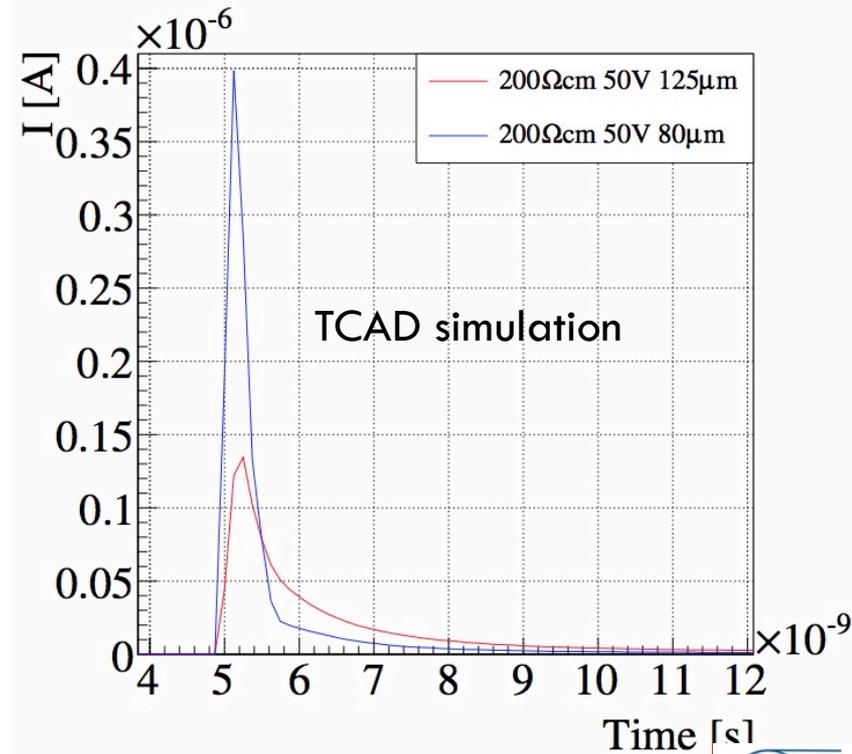
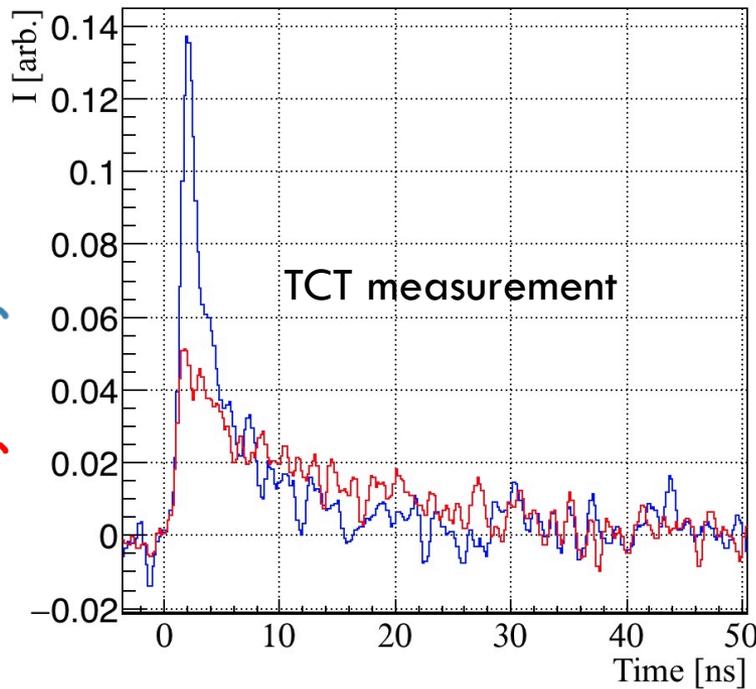
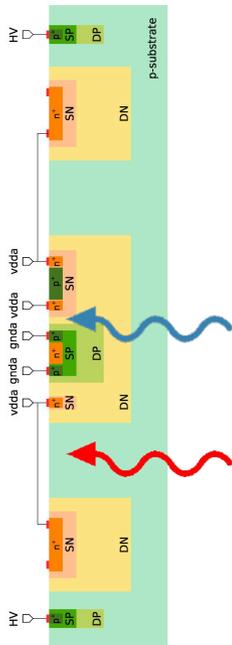


HV-CMOS H35DEMO Pixel Sensor

TCT measurements – Top surface scan

11

- Charge collection (efficiency) within one pixel in a 200 Ohm*cm sample
 - ▣ Laser beam focused on the **middle of the pixel middle diode** VS **between pixel collection diodes**



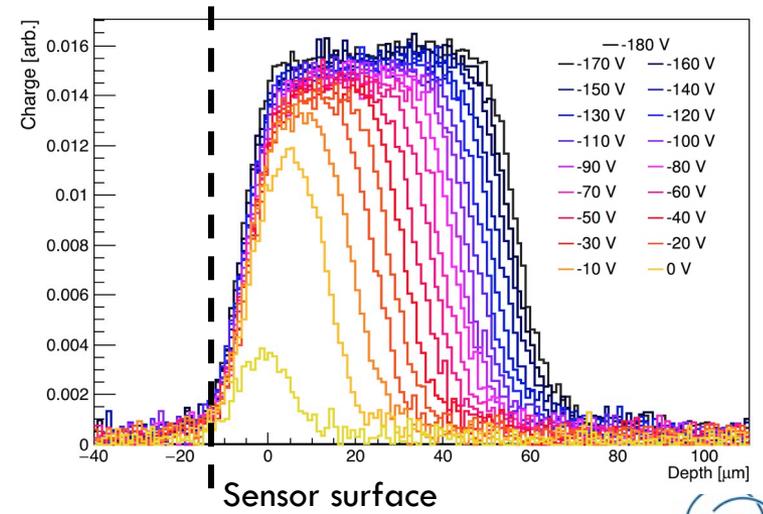
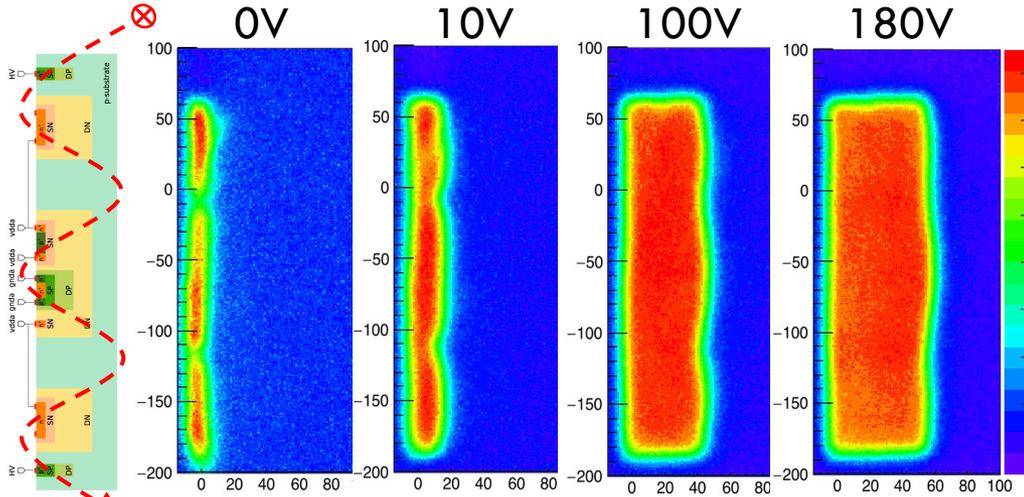
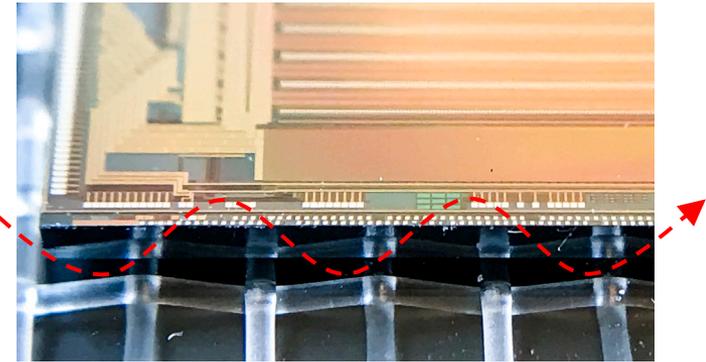
HV-CMOS H35DEMO Pixel Sensor

Edge TCT measurements – Edge surface scan

12

- **Edge laser scans** on the device allows to simulate different bulk depth interactions (infrared laser)
 - ▣ Hits inside the depletion zone will create a faster charge collection (and a higher collection within a small integration time)
 - ▣ Voltage scans shows how the depletion zone grows

⊗ 1.06 μm laser



HV-CMOS H35DEMO Pixel Sensor

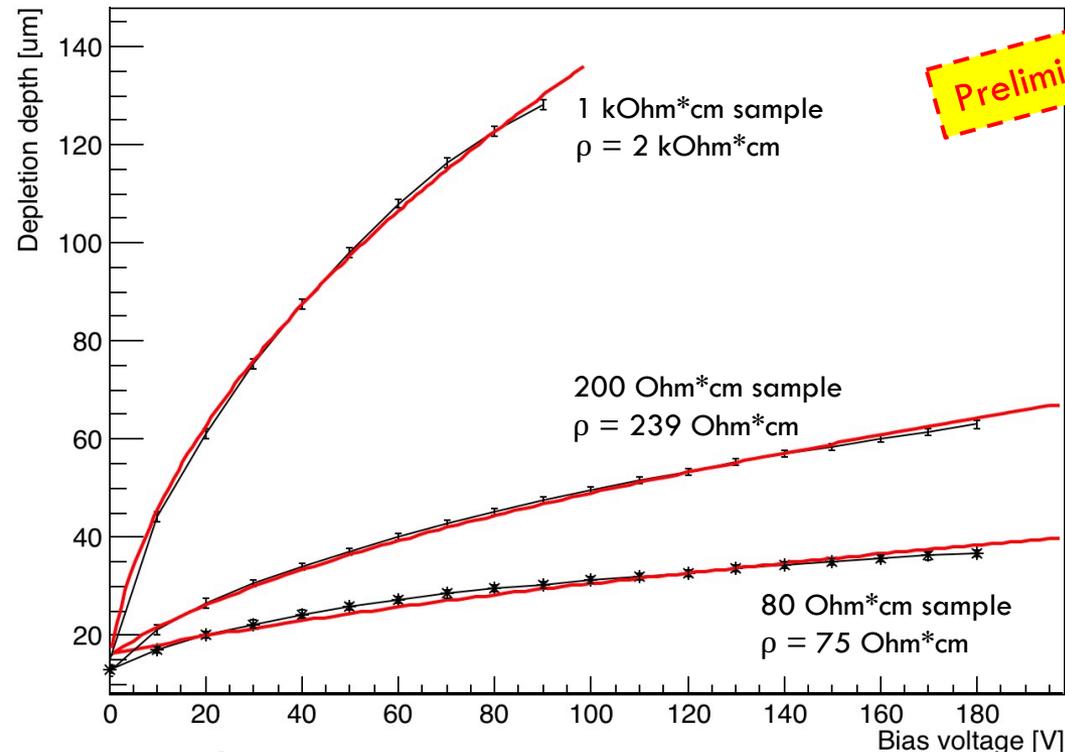
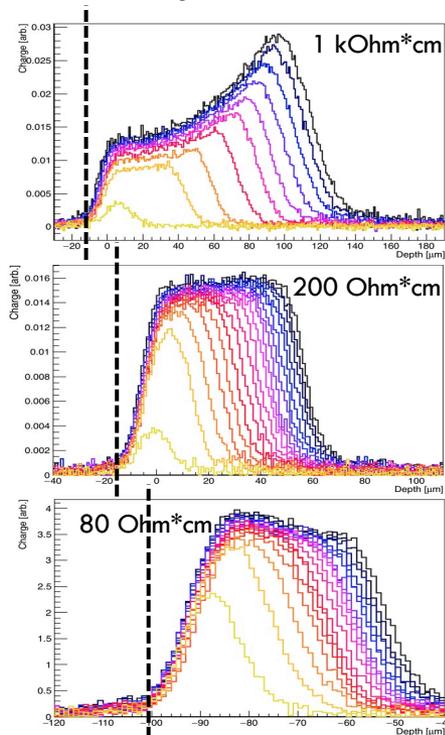
eTCT measurements – Depletion depth VS Bias

13

□ Depletion depth of sensors with **different resistivities**

▣ Depletion depth fit with $d = 0.3 \cdot \sqrt{\rho \cdot (V_B + V_{bi})}$

■ Agreement with **TCAD** simulations **under verification**



Detector assembly @ UniGE Clean Room

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Dry cabinet

Keysight
B1500A

Probe station

Digital microscope



Accura 100
Flip-chip machine

Vortex based chiller

Dr. Benoit

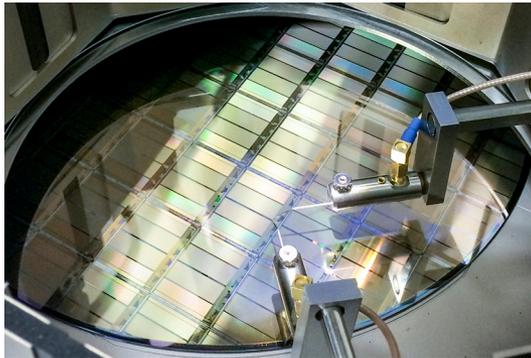
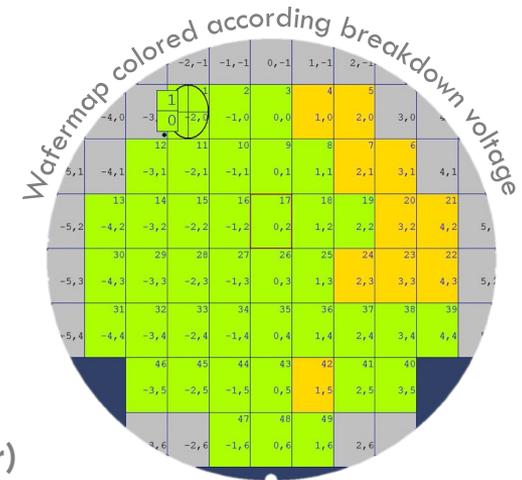
mvicente@cern.ch 25/05/17

H35DEMO wafer probing

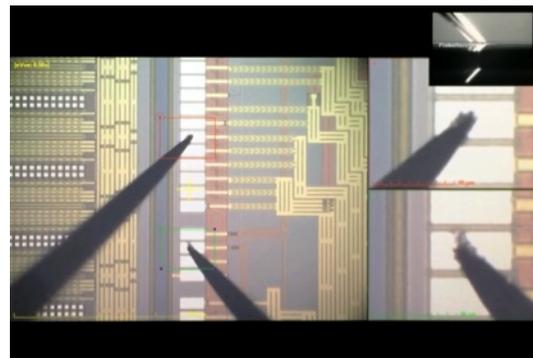
HV-CMOS IVs

15

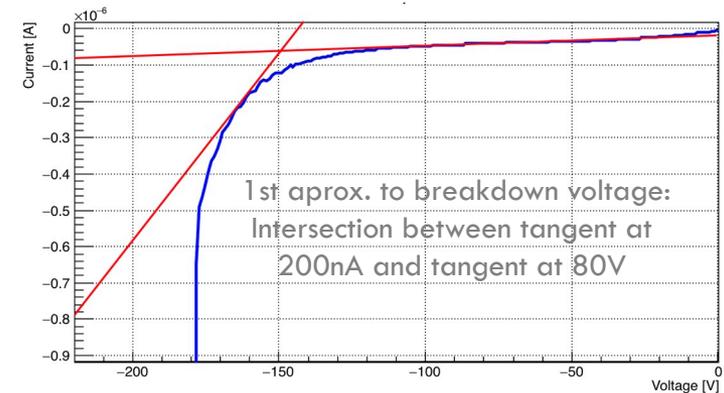
- **Semi-automated** operation wafer prober
 - ▣ Thermal Chucks from **-60°C** to 300°C
 - ▣ XYZ Resolution: **0.2 μm**
 - ▣ **Auto XYZ** and **theta correction** for sub-micron stepping
 - ▣ **Automatic** die size measurement and **wafer mapping tool**
- Programmable tests over full wafer
 - ▣ Current vs Voltage on each (sub)die automatically (**~50 devices/hour**)



H35DEMO wafer with probes positioned



Probes positioned on HV pads

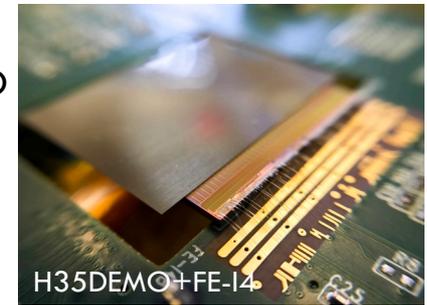


Flip-chip for CCPDs

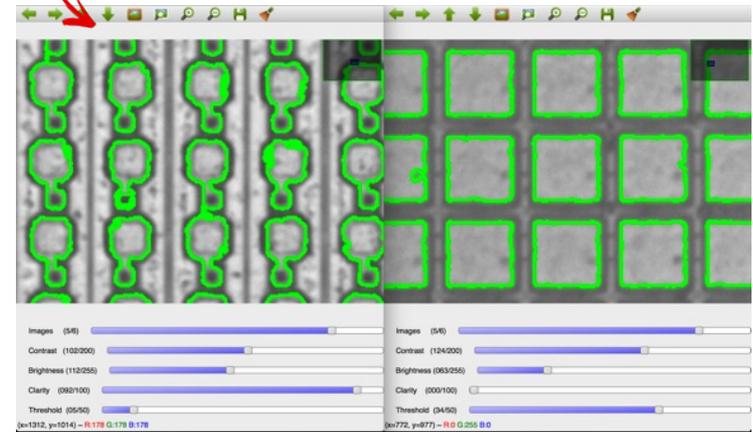
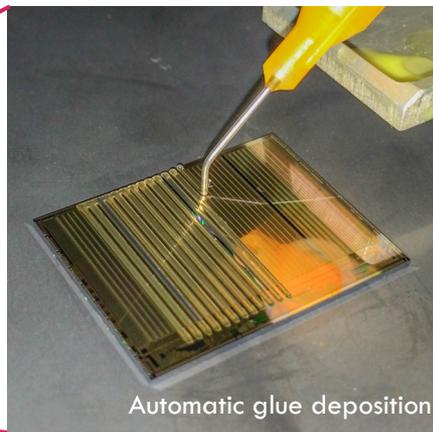
H35DEMO + FE-14

16

- Heating up to **400 degC** and force applied by bonding arm up to **100 kgf**
 - ▣ H35DEMO+FE-14: **100 degC** (for **6 min**) and **5N bonding force**
 - **Automatic glue (Araldite 2011 epoxy resin) deposition** on H35DEMO
- Post bonding accuracy **~1 μm** achieved
 - ▣ < 0.5 μm (theoretically)
 - ▣ **PixelShop** pattern-recognition program to guide alignment



Set Accura 100

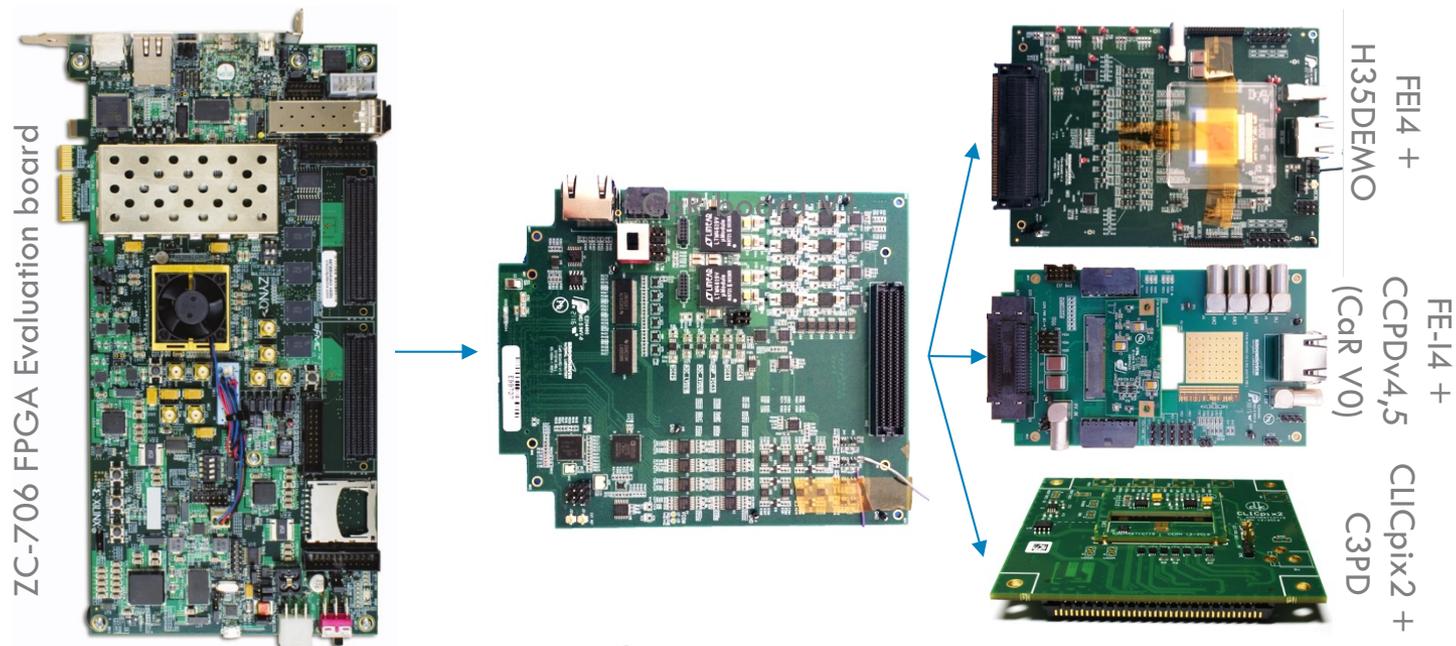


CLICpix (left) and CCPDv3 (right) pixel pads

CaRIBOu System

HV-CMOS DAQ – [GITLAB LINK](#)

- A **FPGA based modular** readout system for silicon detectors
 - ▣ Developed at **BNL** with collaboration from **UNIGE** and **CERN** for **ATLAS** and **CLIC**
 - ▣ **Modular architecture** allows for integration of **new readout chips and sensors**
 - Adrian's talk (CERN): <http://indico.ihep.ac.cn/event/6387/session/38/contribution/24>
 - Hongbin's talk (BNL): <http://indico.ihep.ac.cn/event/6387/session/52/contribution/260>

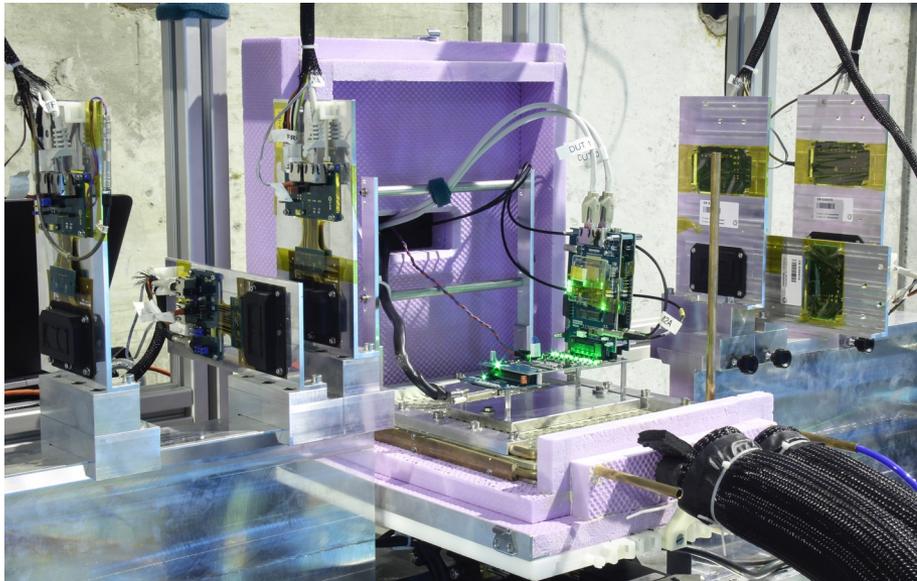


Testbeam results

The FE-I4 UniGE Particle Telescope

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- **FE-I4b** based telescope
 - ▣ "Permanently" installed at **CERN SPS H8** testbeam hall
 - ▣ 6 planes of double FE-I4b modules (HSIO/RCE redout) (+ 2 Mimosa26 planes being installed)
 - ▣ Current: **8x12 μm** . With Mimosa26 planes: **2-3 μm**
 - ▣ Cold DUT box (down to **-20 degC @ DUT**)



FE-I4b UniGE telescope with CaR board V0.1 and 2x CCPDv4 as DUT



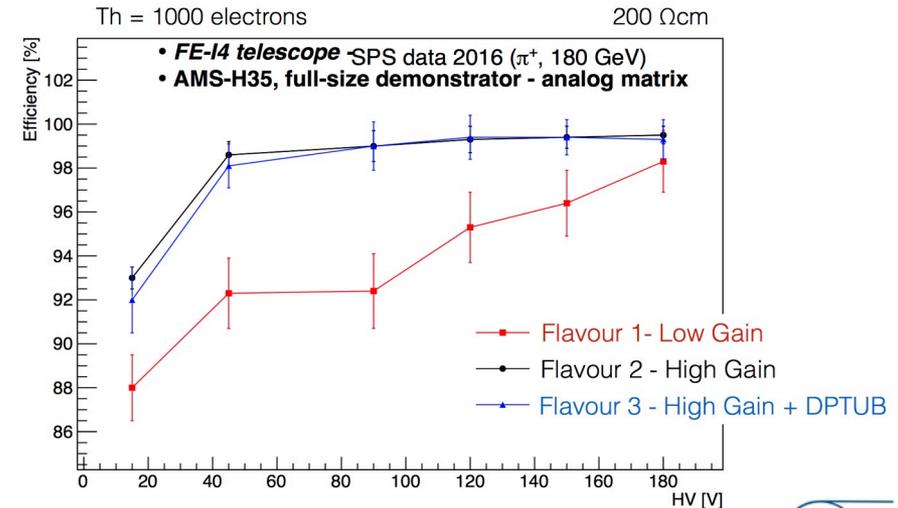
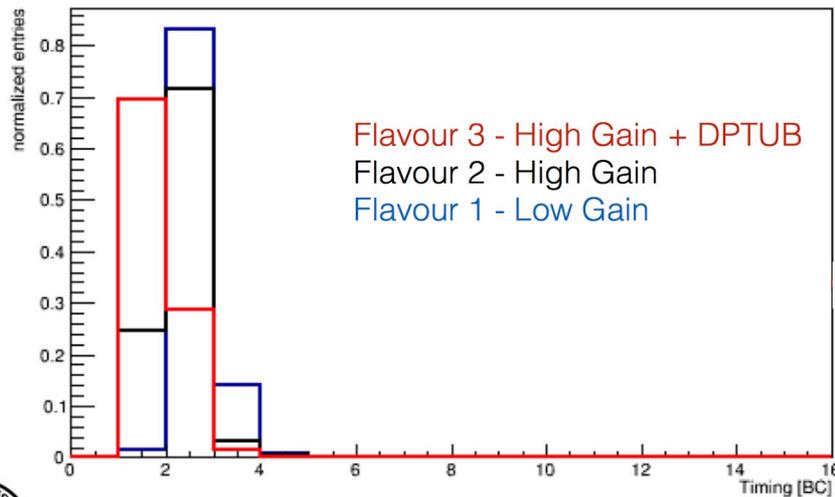
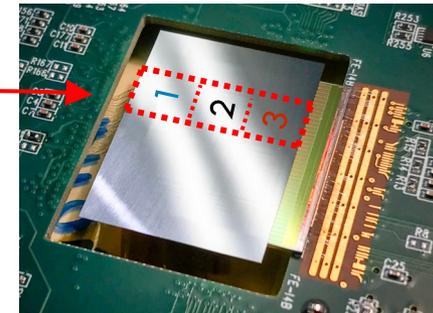
CaR board V1 with FE-I4 | H35DEMO sample

H35DEMO Testbeam results

CERN SPS - Nov 2016

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- 200 Ohm*cm H35DEMO Analog Matrix 1 studied
 - Caribou H35DEMO 01 sample
 - CERN SPS 180 GeV pions beam
 - 1000 e⁻ FE-I4 threshold
 - 99% of collected charge within 50 ns (left plot)
 - 99% efficiency for bias voltages > 90V (right plot)



H35DEMO Testbeam results

Fermilab TestBeam Facility – 2017

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□ Testbeam campaign at **FTBF** – IL/USA

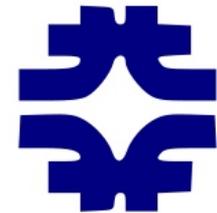
- 120 GeV protons beam
- Samples with 4 different resistivities
 - + voltage and threshold scans

□ Preliminary results!

- High efficiency for all 3 pixel types in both analog matrices
 - Some samples with **non uniformity** in the efficiency
 - Cross-section measurements shows a chip gap variation of $\sim 7\mu\text{m}$

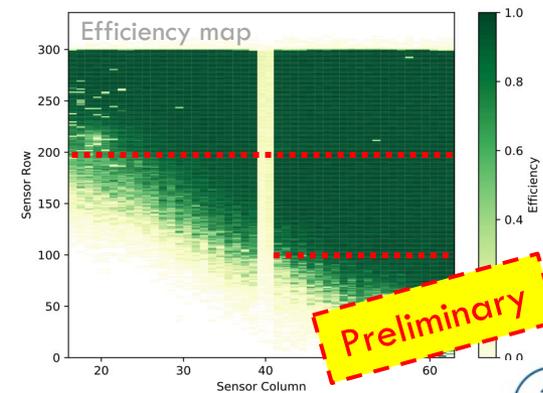
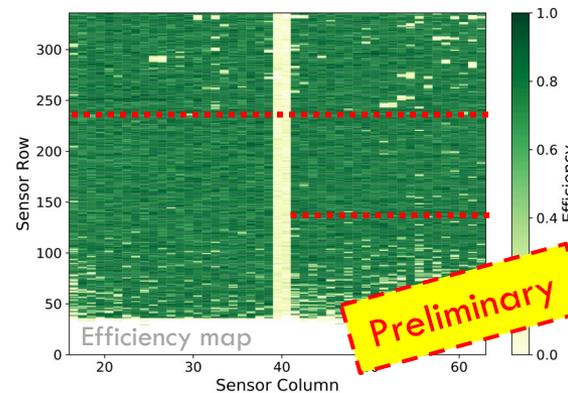
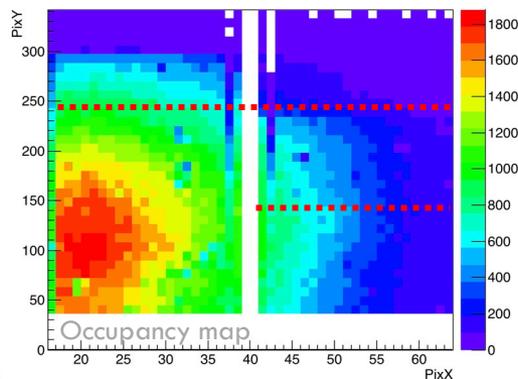


Argonne
NATIONAL
LABORATORY



Fermilab

Thanks for our friends at Fermilab and Argonne!



Conclusions

and overview

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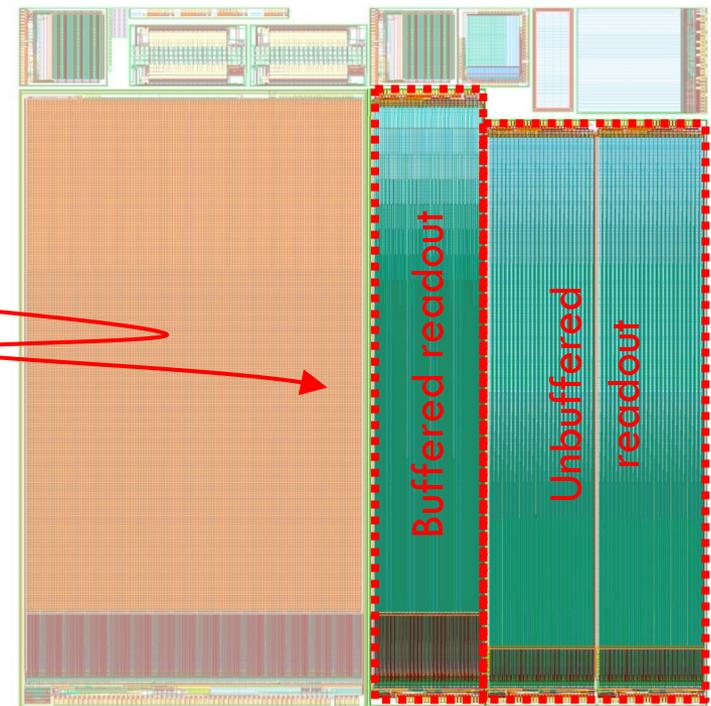
- ATLAS inner tracker detector will be upgraded for the LHC high lumni upgrade
 - **New all-silicon inner tracker** → large area of silicon → \$\$\$
- **HV-CMOS** based sensor/readout chip is a candidate for the new detectors
 - **H35DEMO** HV-CMOS detector demonstrator chip
- **TCAD simulations** are done to evaluate sensor performance
 - **Top and edge TCT measurements** are done in order to verify achieved performance
 - **Agreement** between simulation and measurements is **satisfactory**
 - Results indicates **better performance** on sensors with **higher bulk resistivities** and **back biased** devices
- **Assembly** of HV-CMOS sensor with readout ASIC
 - **H35DEMO Wafer IV scan** ensures a good production **yield** and saves **time/money**
 - **H35DEMO + FE-I4b flip-chip** gluing using Araldite 2011 **Epoxy Resin** → cheaper production
- **Testbeam results** using the **CARIBOU** DAQ system
 - First sample tested at SPS indicates **high efficiency** (~99%) with **99% of the charge** collected in **50 ns**
 - **Fermilab** testbeam **data** is still **under analysis**. **Good efficiency** on pixel matrix is **already observed**



Future and next steps

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- Further tests on capacitively couples pixel (**irradiated**) devices
 - ▣ Cheaper implementation for larger areas by not using bump-bonds
 - ▣ **Pixel sizes < bump-bonds pitch restriction**
- Investigation on **MAPS** (monolithic detectors)
 - ▣ **Standalone** readout matrices of **H35DEMO**
 - Before and after irradiation
 - ▣ New **180nm CMOS demonstrator AtlasPix** chip
 - Previous **180nm prototype** results:
 - Before irradiation <https://aps.arxiv.org/pdf/1603.07798.pdf>
 - After irradiation <https://arxiv.org/pdf/1611.02669v1.pdf>
- Stay tuned for new results =)



谢谢

Thank you

BACKUP



H35DEMO

Analog pixel flavors

Analog Matrix 1

CSA uses a folded-cascode with an nMOS transistor as input device without gain boosting
 > less noise, better radiation tolerance, increased power consumption

Flavour 1	Flavour 2
use linear transistors	use enclosed layout transistors

Analog Matrix 2

CSA uses a folded-cascode with a pMOS transistor as input device

Flavour 3	Flavour 2	Flavour 1
with DPTUB for HV High Gain	without DPTUB for HV High Gain	without DPTUB for HV Low Gain



Flip-chip at UniGE

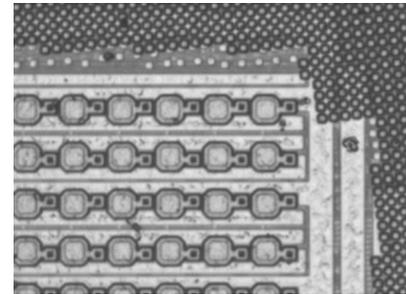
CLICpix + CCPDv3 with PixelShop

25

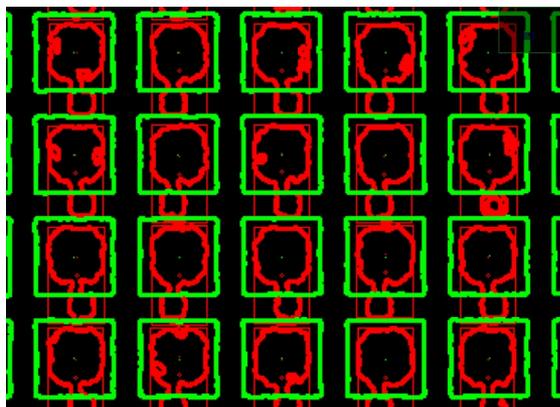
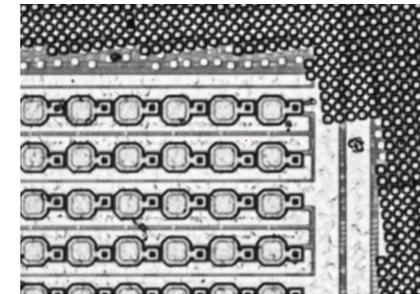
PixelShop

- Pictures from flip-chip digital cameras
 - 2 cameras with field of view of 900x700 μ m
 - 0.37 μ m/pixel
- C++ and OpenCV framework
 - Enhance pictures contrast for better contour finding
 - Calculate offset between contour geometric center

CLICpix original picture

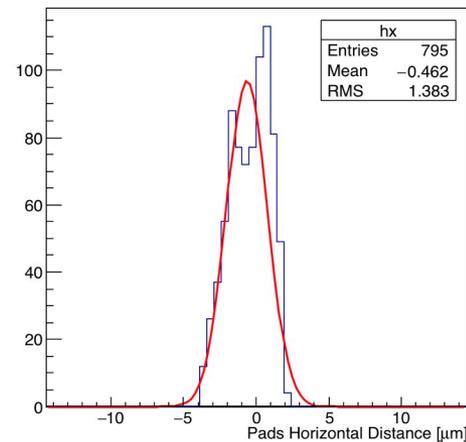


CLICpix edited picture

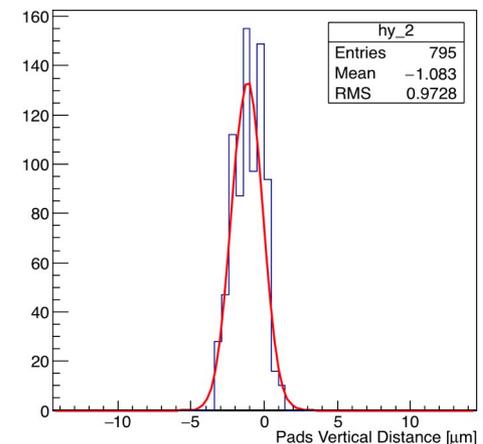


Pixel pads contours
CLICpix and CCPDv3

Horizontal pads offset



Vertical pads offset



CaRIBOu System

CaR board resources

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- 8 × general purpose power supplies with monitoring capabilities
- 32 × adjustable voltage output (0 — 4 V)
- 8 × current output (0 — 1 mA)
- 8 × voltage input (0 — 4 V)
- ADC (16 channels, 65 MSPS/14-bit)
- 4 × injection pulser
- I2C bus
- TLU RJ45 input (clock and trigger/shutter)
- general CMOS signals (10 × outputs, 14 × inputs)
 - with adjustable voltage levels (0.8 - 3.6V)
- 17 × LVDS pairs



FE-I4 + H35DEMO @ Fermilab 2017